

## REMARKS

In the May 7, 2004 Office Action, the Examiner:

1. Objected to claim 1-2, 33-34 as vague in that claims 1, 2, 33 and 34:
  - a. Recite the phrase "melt or semi-melt;"
  - b. Recite the word "it;"
2. Objected to claim 17 because it contains a misplaced parenthesis.
3. Rejected claims 1-9, 12-26, 33-41, 44-58 under 35 U.S.C. § 102(e) as anticipated by Yamakazi (U.S. Patent No. 6,693,044).
4. Objected to claims 10-11, 27-32, 42-43, 59-61 as being dependent on a rejected base claim.

Applicants have amended claims 1-2, 17, and 33-34 to address the Examiner's objections. Applicants have also amended claims 1, 2, 33, and 34 to more clearly point out what the inventors consider to be their invention. With respect to the Examiner's rejections, Applicants respectfully traverse.

The Examiner rejected claims 1-9, 12-26, 33-41, 44-58 as anticipated by Yamakazi. The Examiner stated that Yamakazi discloses a method that is claimed in independent claims 1, 2, 33 and 34. The Examiner states that Yamakazi discloses "a step of performing focused-light annealing" and cites to col. 6, line 62-67 in Yamakazi as support. Yamakazi states at col. 6:62-67 to col. 7:1-3:

Next, crystallization of the first amorphous silicon film 101 is carried out by a heat treatment. This heat treatment is carried out in an inert gas atmosphere, a hydrogen atmosphere, or an oxygen atmosphere at a temperature of 500 to 1000 degrees C. for 12 to 72

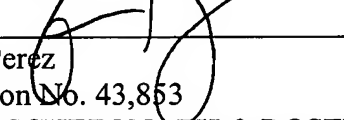
hours. Although the effect becomes great as the heating temperature becomes high, in view of heat resistance of the substrate, it is necessary that the temperature is made not higher than the distortion point of the substrate to be used.

This passage does not mention any "focused-light annealing." Yamakazi does make reference to "laser annealing" at col. 7:10-12, however, Yamakazi makes no reference to "focused-light annealing." Applicants note the problems with laser annealing that were described in the Background in the Invention. To further clarify the claims, Applicants have amended claims 1, 2, 33 and 34 to recite "focused-light lamp annealing."

Applicants respectfully submit that Yamakazi does not anticipate claims 1-9, 12-26, 33-41, 44-58. Favorable reconsideration is respectfully requested.

Respectfully submitted,

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